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## Sill Optics 343-355nm 1X - 3X Variable Beam Expander, S6EXZ5311-574

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Stock #70-172 **2 In Stock**

⊖ 1 ⊕ C\$3,444.<sup>00</sup>

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### General

S6EXZ5311-574 **Model Number:**

Beam Expander **Type:**

Continuous Variable Magnification **Style:**

### Physical & Mechanical Properties

**Length (mm):**

85.18

Weight (g):

0.30

Housing Diameter (mm):

47.00

Pointing Accuracy (mrad):

<1

## Optical Properties

Entrance Aperture (mm):

10.50

Exit Aperture (mm):

20.00

Expansion Power:

1X - 3X

Substrate:

Fused Silica

Transmission (%):

>97

Coating:

355

Design Wavelength DWL (nm):

355

Wavelength Range (nm):

343 - 355

Coating Specification:

343nm - 355nm R < 0.20% - low absorption

Damage Threshold, By Design:

1.0 J/cm<sup>2</sup> per 1ns pulse at 50Hz

Divergence Adjustment:

Rotating Optics

## Threading & Mounting

Mounting Threads:

M30 x 1.0

## Regulatory Compliance

Certificate of Conformance:

[View](#)

## Product Details

- 1X–3X and 1X–8X Variable Magnification
- High Damage Thresholds up to 5.0 J/cm<sup>2</sup> (1ns, 50Hz)
- [Motorized Magnification](#) Versions Available

Sill Optics Variable Beam Expanders are designed to optimize focus diameter, focus position and beam propagation within a laser system. All optical elements within these beam expanders are constructed from fused silica substrates featuring a special low-absorption coating to minimize thermal effects. These beam expanders can withstand the high thermal strain of small beam diameters and provide stable and reliable performance while utilizing high average or high peak power lasers. Sill Optics Variable Beam Expanders are available for use with 355nm, 532nm, and 1064nm design wavelengths and feature high damage thresholds for pulsed lasers up to 5.0 J/cm<sup>2</sup> (1ns, 50Hz). These beam expanders are ideal for high power laser applications where magnification changes may be required, such as prototyping, solar cell manufacturing, confocal microscopy, or R&D.